In the claims:

Claims 1-21 were examined.

Claim 3 was cancelled

Amend claims 1-2, 4-6, 8-10 and 13-21 as follows:

1. (currently amended) An apparatus ~~for~~ to apply a selected masking pattern to a ~~workpiece coated with a photosensitive~~ photoresist layer[[,]] on a workpiece to prevent exposure of ~~select~~ masked regions of the ~~photosensitive~~ photoresist layer, comprising:

a workpiece pre-aligner ~~for~~ disposed to movably ~~supporting~~ support and ~~aligning~~ initially align the workpiece;

a rotation device to engage the workpiece and to rotate the workpiece while being masked; and

an ink delivery device disposed to be arranged to be in communication with the ~~photosensitive~~ photoresist layer of the workpiece ~~for providing a masking pattern of~~ to apply opaque ink to form the selected masking pattern on ~~a photosensitive~~ the photoresist layer in cooperation with the workpiece pre-aligner as the workpiece is rotated;

wherein the opaque ink is opaque to a wavelength of radiation that will activate the photoresist layer on the workpiece.

2. (currently amended) An apparatus according to claim 1 further comprising ~~, wherein the ink delivery device is connected to~~ a control unit in communication with the workpiece pre-aligner, the rotation device and the ink delivery device to control ~~that controls~~ the ~~deposition~~ application of ink onto the ~~photosensitive~~ photoresist layer in the selected masking pattern.

3. (cancelled)

4. (currently amended) An apparatus according to claim 1, wherein the workpiece pre-aligner includes a movable arm ~~capable of engaging and supporting~~ disposed to engage and support the workpiece, wherein the movable arm is in operative communication with a workpiece stage of a lithography tool.

5. (currently amended) An apparatus according to claim 1, wherein the ~~photosensitive~~ photoresist layer is a negative- tone dry film resist.

6. (currently amended) An apparatus according to claim 2, wherein the ~~control unit is connected to the~~ workpiece pre-aligner ~~so that~~ provides information about the ~~workpiece~~ state of the workpiece ~~can be provided~~ to the control unit .

7. (original) An apparatus according to claim 6, wherein the control unit is connected to a main controller of a lithography system.

8. (currently amended) An apparatus according to claim 1, wherein the workpiece pre-aligner is ~~part~~ a component of a lithography tool.

9. (currently amended) An apparatus according to claim 1, wherein the ink delivery device delivers fast-drying ink that adheres to ~~MYLAR®~~ polyethylene terephthalate polyester.

10. (currently amended) An apparatus according to claim 1, wherein the ink delivery device is ~~movable~~ disposed to be moved over the workpiece.

11. (original) An apparatus according to claim 2, wherein the controller is programmable ~~so as to form a desired~~ to control the execution of the selected masking pattern on the ~~workpiece~~ photoresist layer of the workpiece.

12. (original) An apparatus according to claim 1, wherein the ink delivery device includes an inkjet head.

13. (currently amended) A method [[~~of~~]] for selectively masking a ~~photosensitive workpiece~~ photoresist layer on a workpiece, the method comprising the steps of:

selecting one or more regions of the ~~photosensitive workpiece surface~~ photoresist layer on the workpiece that are to ~~remain unexposed~~ be masked;

rotating the workpiece during masking; and

masking the one or more ~~select~~ selected regions of the photoresist layer of the workpiece, while the workpiece is rotated, with a layer of ink that is opaque to a wavelength of radiation that ~~activates~~ will activate the ~~photosensitive workpiece~~ photoresist layer on the workpiece.

14. (currently amended) A method according to claim 13, wherein the masking step includes the step of depositing the layer of ink with an inkjet head.

15. (currently amended) A method according to claim 14, further includes the step of ~~including~~ programming an inkjet head control unit connected to the inkjet head to control the deposition of the layer of ink.

16. (currently amended) A method according to claim 15, wherein the method further includes the step of ~~including~~ coordinating the deposition of the layer of ink with the movement of the workpiece.

17. (currently amended) A method according to claim 14, wherein the masking step ~~the workpiece~~ includes the step of moving the workpiece and inkjet head relative to each other with the wafer underneath the inkjet head.

18. (currently amended) A method according to claim 13 wherein the workpiece is substantially round ~~and has~~ having an edge, and the one or more ~~select~~ selected regions ~~include~~ includes a narrow annulus adjacent the workpiece edge.

19. (currently amended) A method according to claim 13, wherein the masking step includes the step of forming one or more alphanumeric characters.

20. (currently amended) A method according to claim 13, wherein the masking step includes the step of forming a bar code.

21. (currently amended) A method according to claim 13, wherein the ~~masking is formed~~ the one or more selected regions are outside of an area of the workpiece where exposure fields are to be formed on the workpiece.